



2nd LATAM MEETING ON GREEN
AMMONIA AND POWER-to-X



MatER
Materials Science and
Renewable Energies Group

Aluminum-Doped Amorphous Silicon Carbide Thin Films as Photocathode for Green Ammonia Production

L. Sanchez^{1, *}, F.Bravo¹, R.Pulido^{1,2}, J.A. Guerra¹, K. Nanda²

¹Pontifical Catholic University of Peru, Physics Department, Lima, Peru.

²Pontifical Catholic University of Peru, Chemical Department, Lima, Peru.

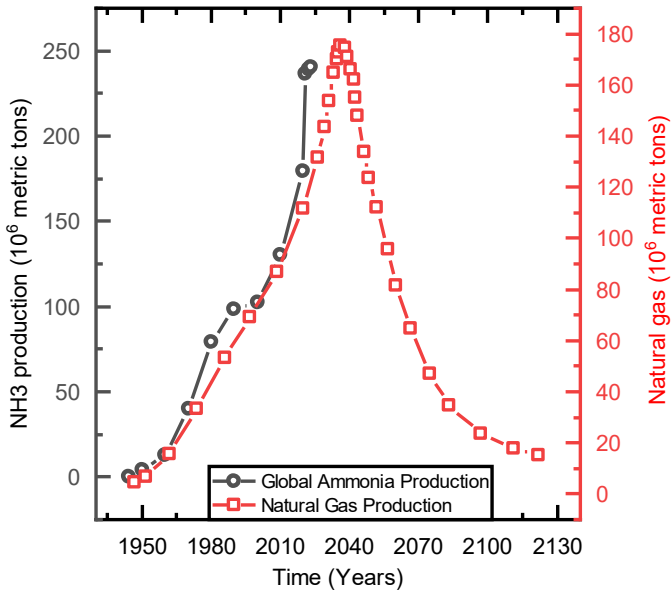
*francisco.sanchezs@pucp.edu.pe



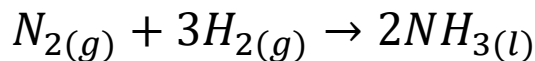
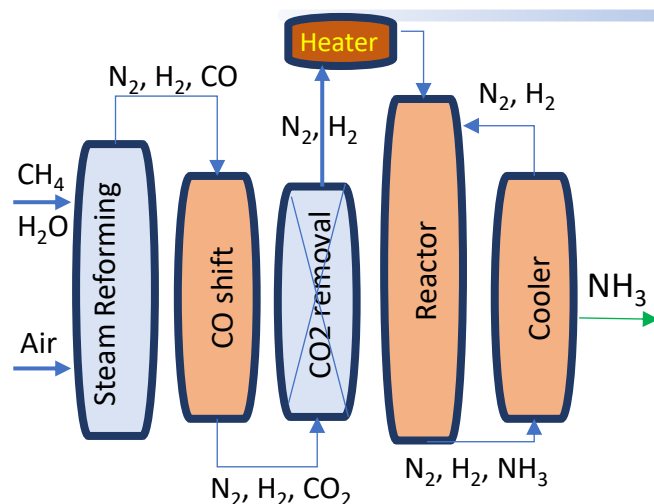
CONCYTEC
CONSEJO NACIONAL DE CIENCIA,
TECNOLOGÍA E INNOVACIÓN



Introduction



Palma, V. et al. *Nanomaterials*,(2020),1-56,10(8)



Palma, V. et al. *Nanomaterials*,(2020),1-56,10(8)

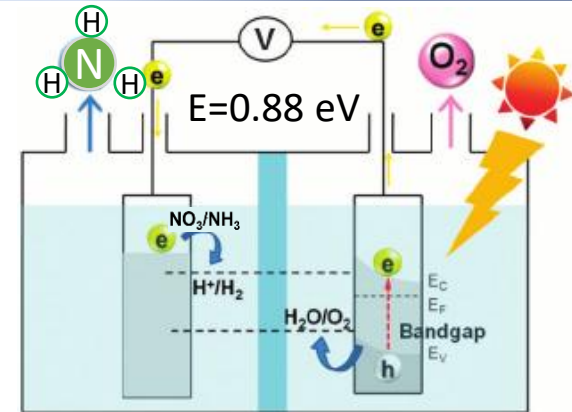
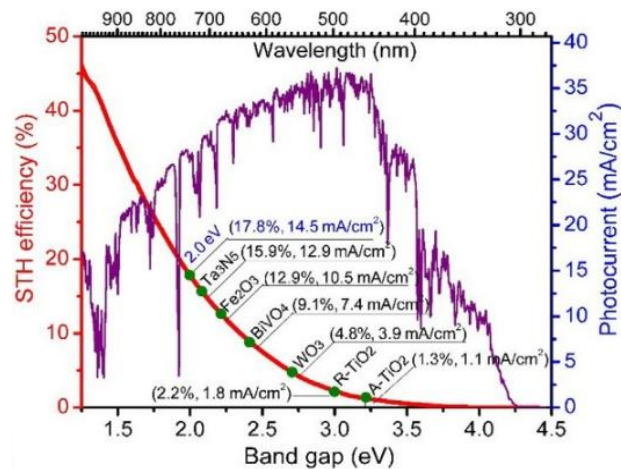


Diagram of the basic principles of Reduction NO_3^- for photoelectrochemical cell

Chen, H. et al. *Chemical Society Review*,(2012),5654-5671,41(17)



Jian et al. *Solar RRL*, 2020,4(7)

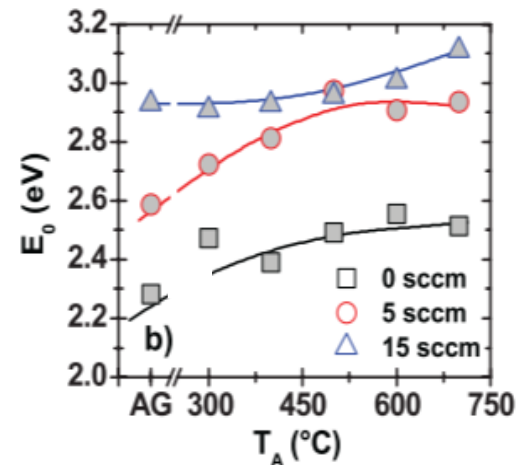
Why a-SiC?

- Abundance and easy reproducible
- Band gap tuning
- Excellent chemical stability

Soltys et al. *Physics and chemist of solid state*(2023),5-16,24(1)

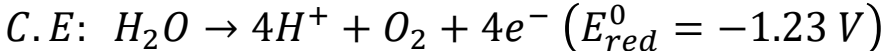
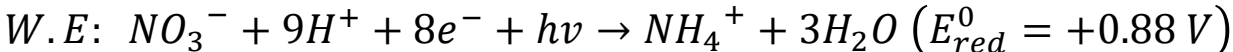
What we aim?

- Physical properties
- Photoelectrochemical properties

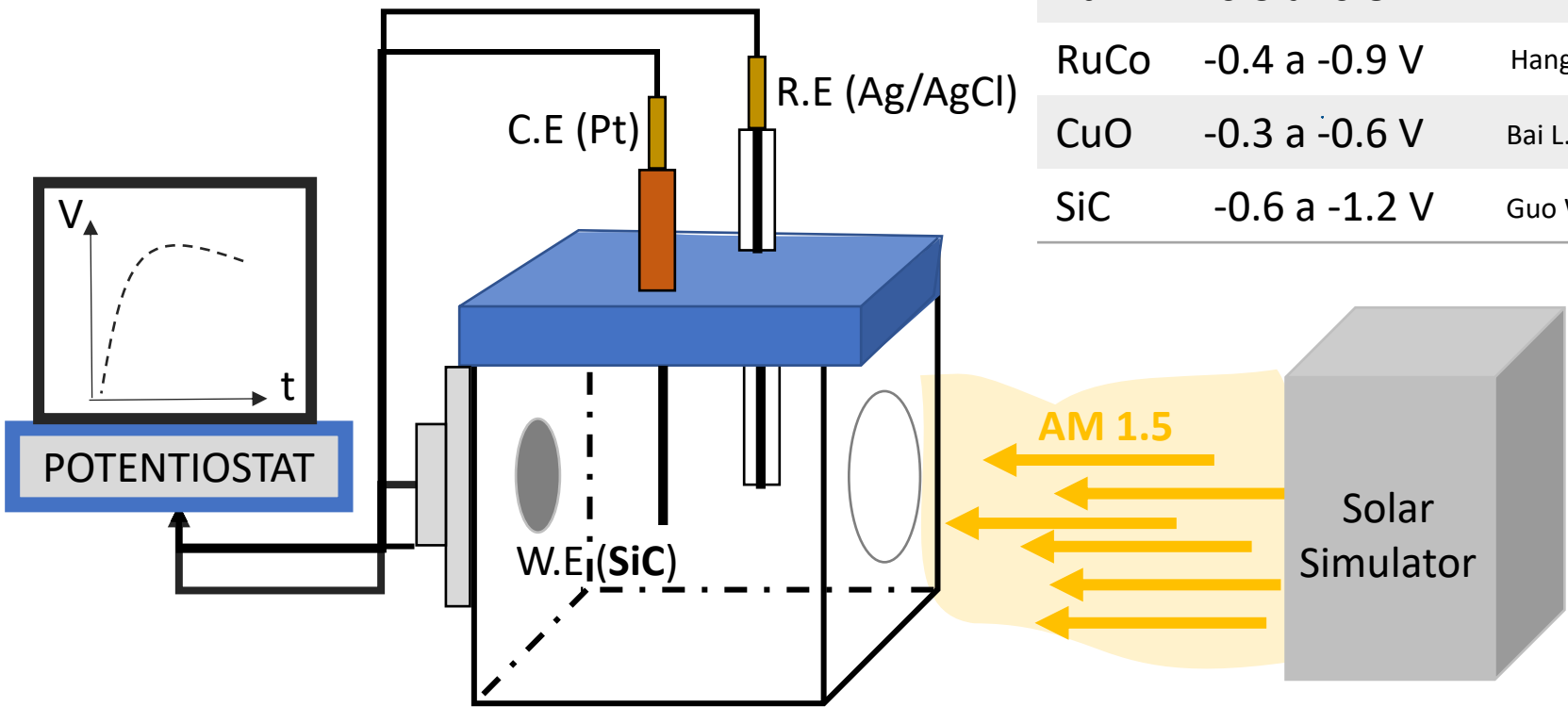


.Guerra et al. *Journal Physics*,2016,49(19)

Potential and Electrochemical Response Analysis



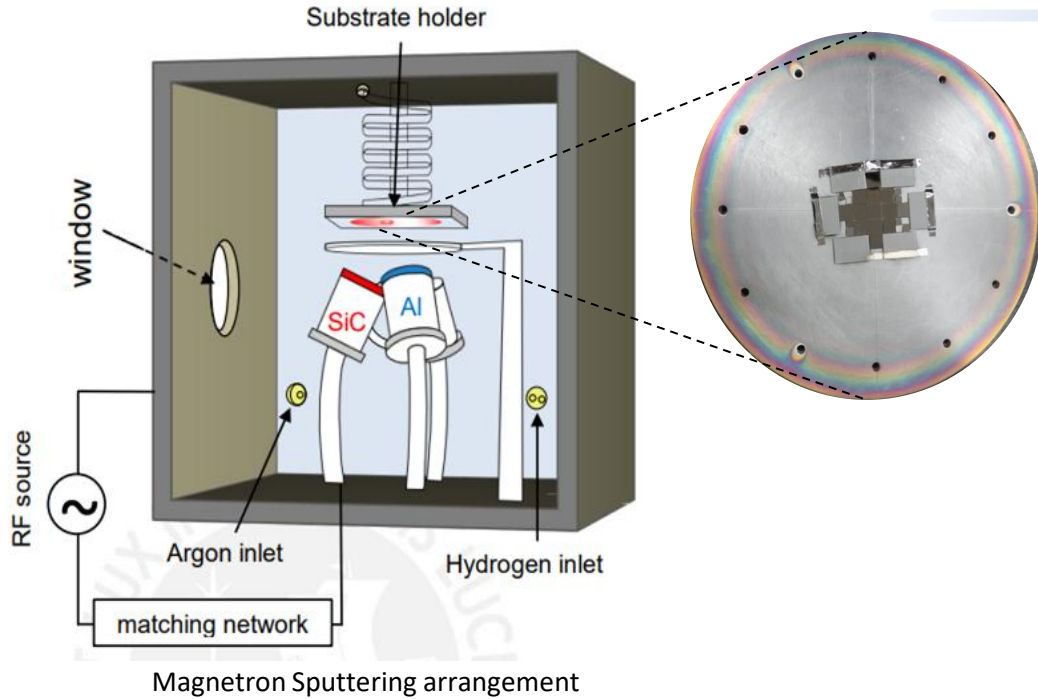
Karamad et al.2022



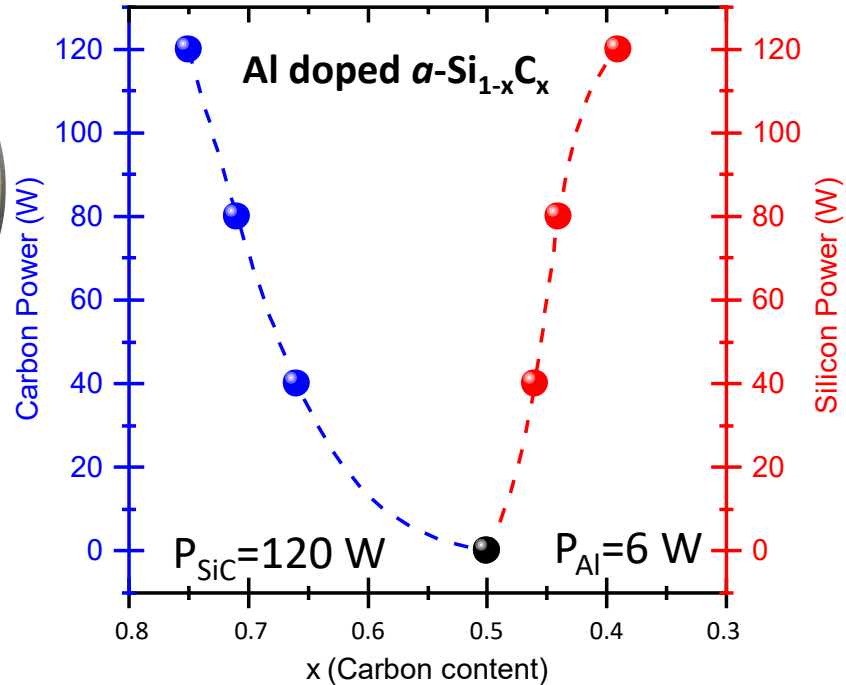
Cathode	Overpotential (η vs Ag/AgCl)	
Pt	-0.3 a -0.8 V	Zhang H. et al 2023
RuCo	-0.4 a -0.9 V	Hang et al.2023
CuO	-0.3 a -0.6 V	Bai L. et al.2021
SiC	-0.6 a -1.2 V	Guo W. et al.2023

Diagram for evaluation photoelectrochemical response

Thin Film Deposition



$$R_{SiC} = 0.045P_{SiC} - 0.53$$



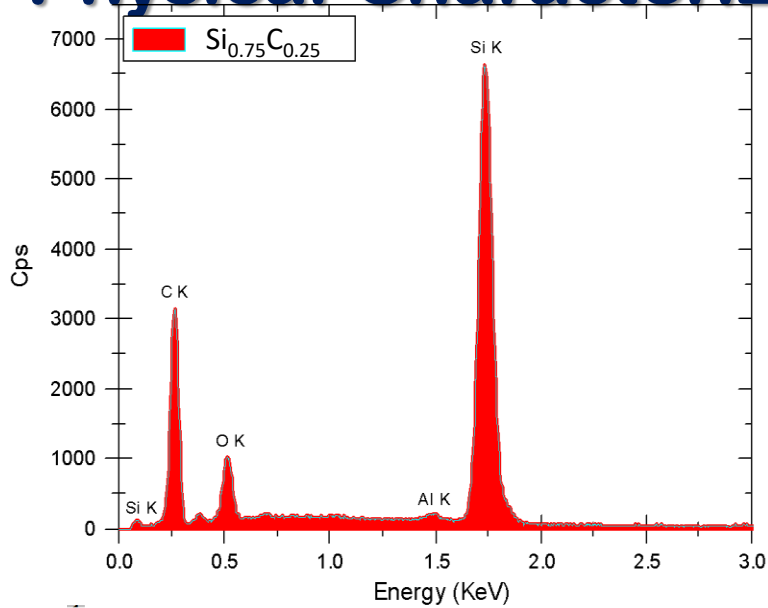
Plot of targets power to get $a\text{-Si}_{1-x}\text{C}_x\text{:Al}$ thin films



Images of sputtered of non-stoichiometric $a\text{-Si}_{1-x}\text{C}_x\text{:Al}$ thin films

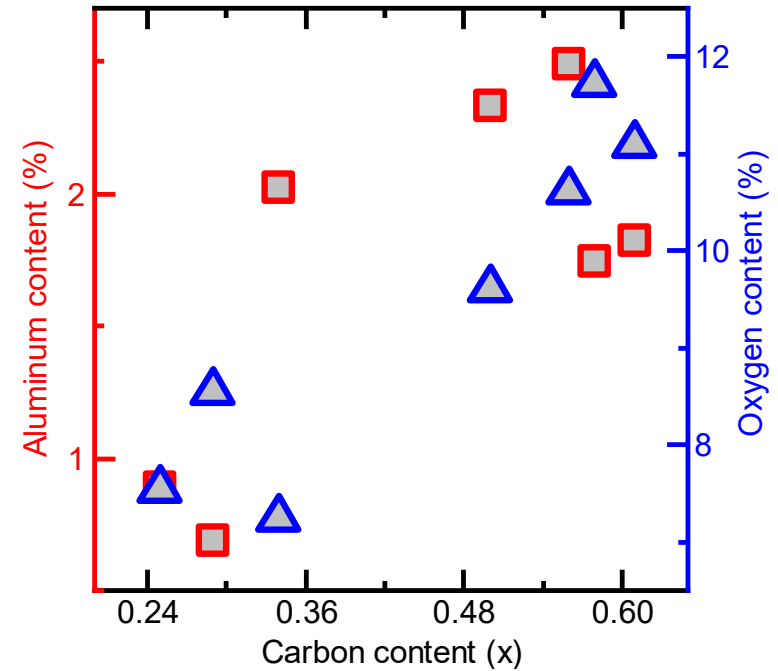
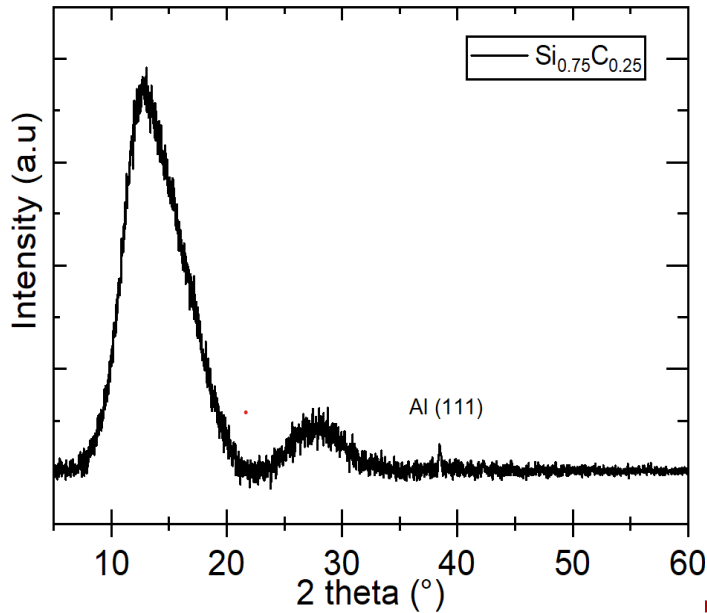
- Base Pressure: $3.5 \times 10^{-7} \text{ mbar}$.
- Active cooling and rotation of substrate holder at 10°C
- Argon flux of 30 sccm
- Deposition time : 45 min.

Physical Characterization

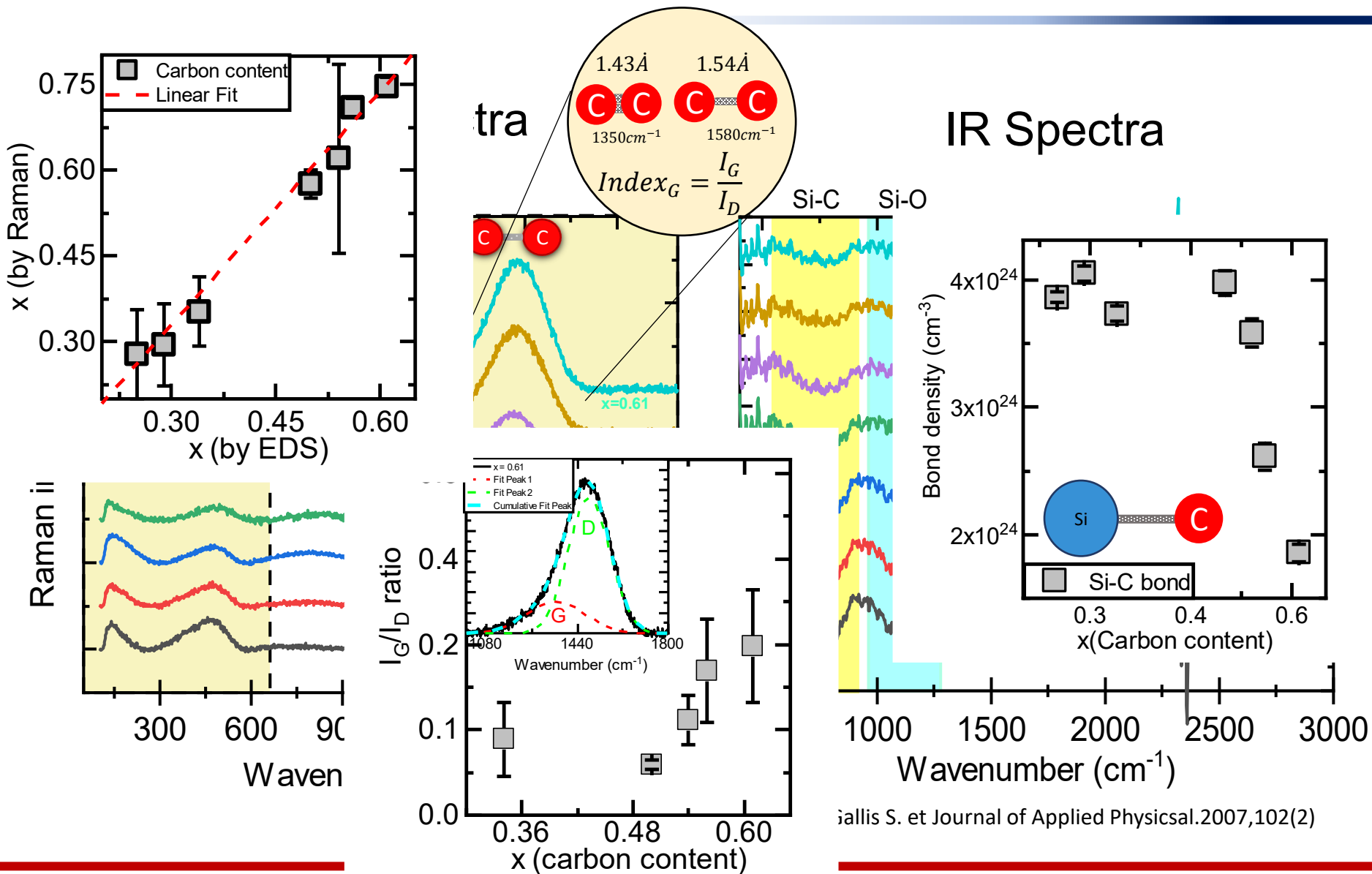


	Chemical composition (Atomic %)			
	Si	C	O	Al
$\text{Si}_{0.75}\text{C}_{0.25}$	66.51	25.06	7.54	0.89
$\text{Si}_{0.75}\text{C}_{0.29}$	61.85	28.91	8.55	0.69
$\text{Si}_{0.64}\text{C}_{0.34}$	57.16	33.07	7.24	2.02
$\text{Si}_{0.50}\text{C}_{0.50}$	41.11	46.95	9.60	2.33
$\text{Si}_{0.44}\text{C}_{0.56}$	34.99	51.90	10.62	2.49
$\text{Si}_{0.42}\text{C}_{0.58}$	33.35	53.15	11.73	1.74
$\text{Si}_{0.39}\text{C}_{0.61}$	30.38	54.91	11.10	1.82

Elemental atomic concentration of samples produced by RF magnetron sputtering.

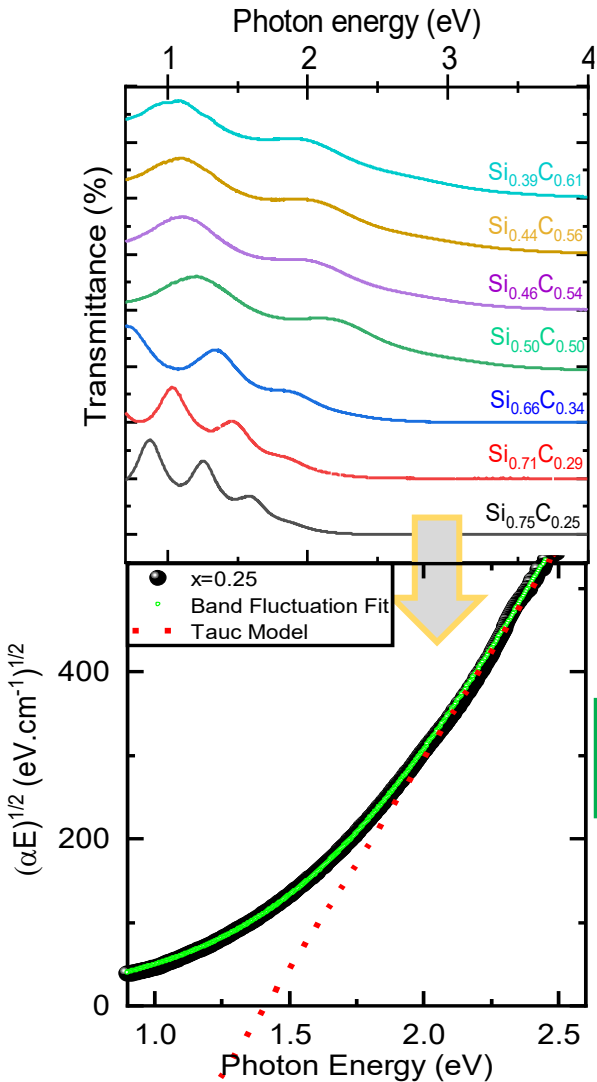


Structure and bonding of a-SiC



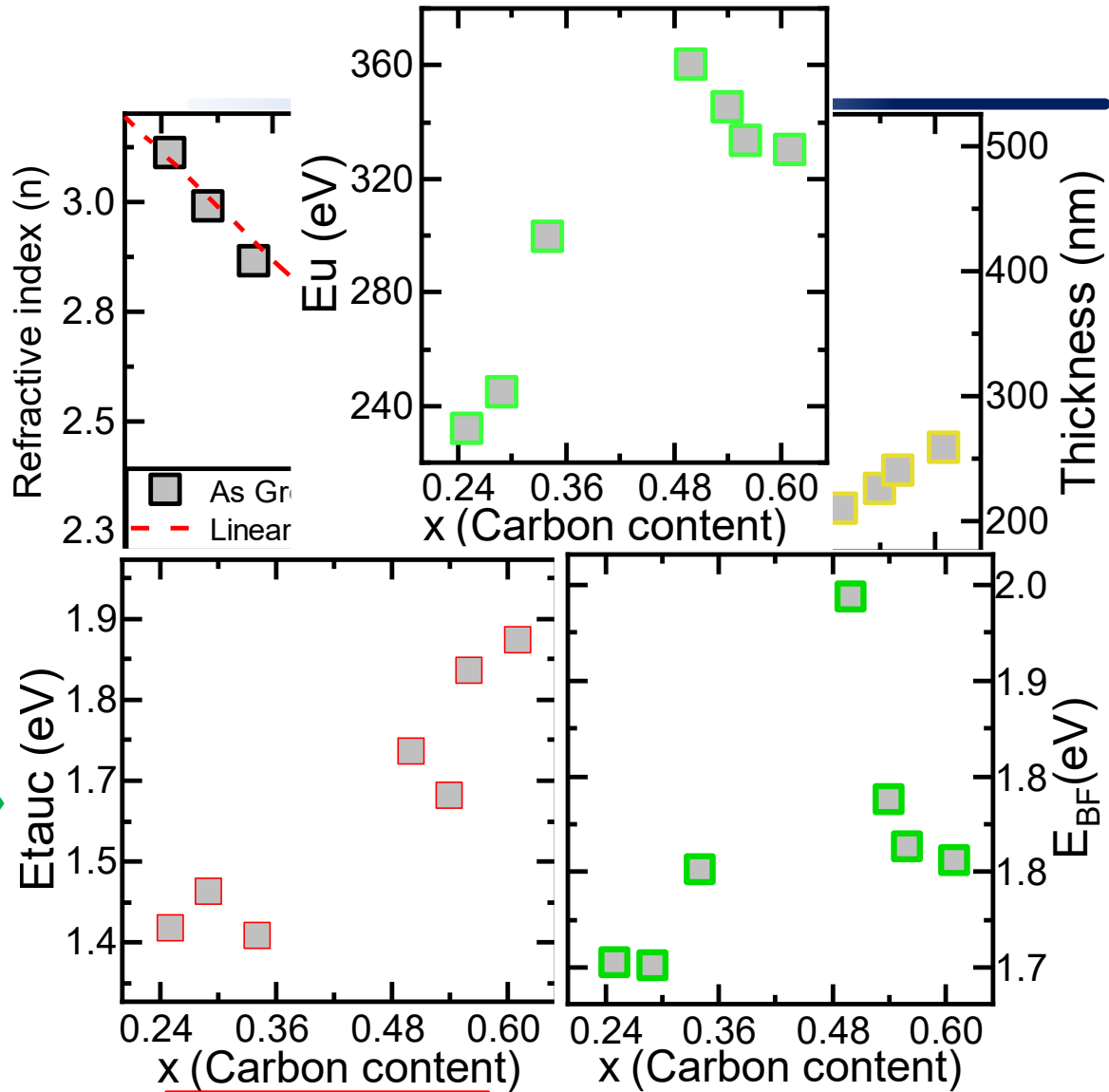
Ballis S. et Journal of Applied Physics. 2007, 102(2)

Optical characterization



K Lizárraga, Journal of Physics Applied 56 (36)

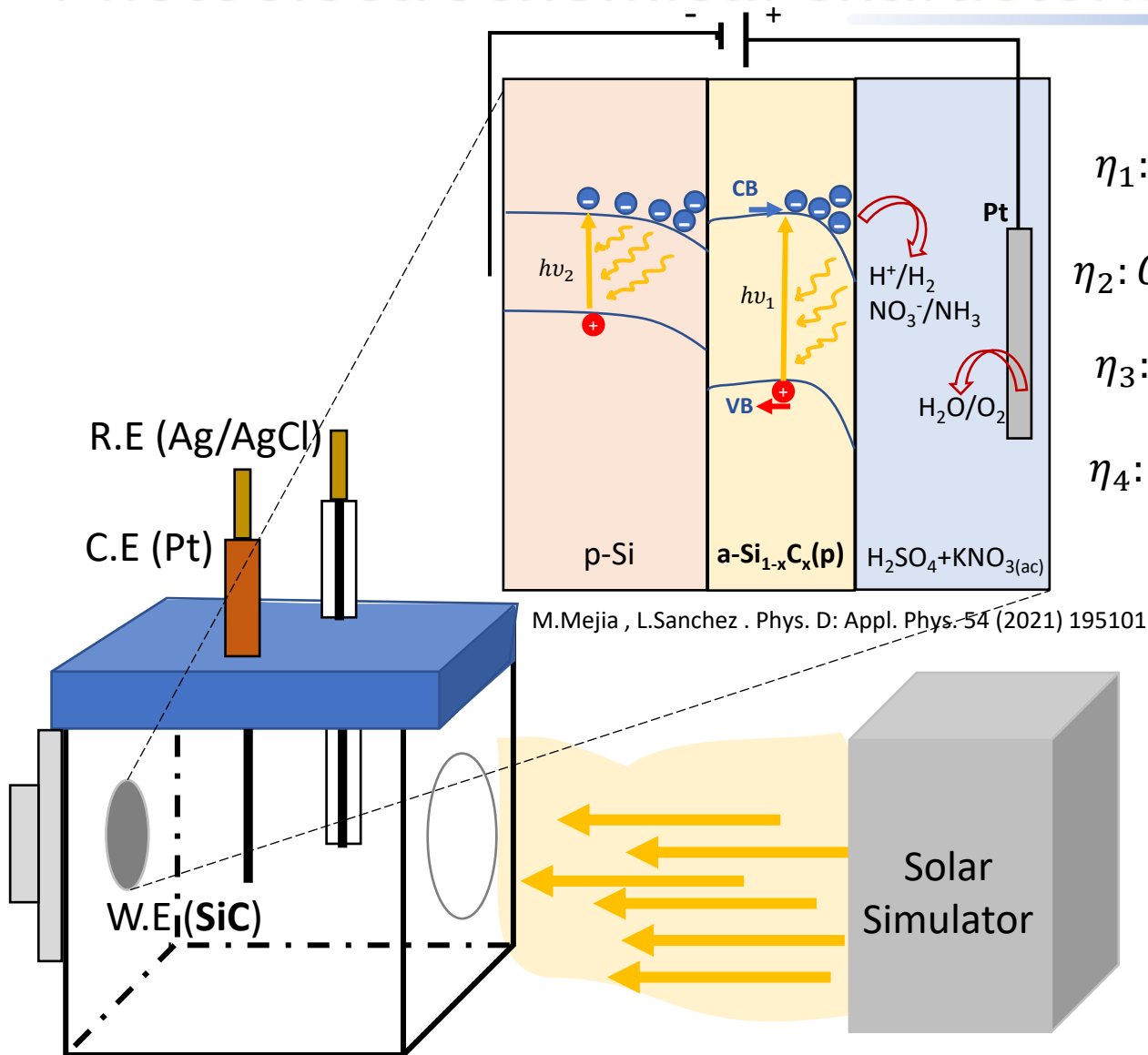
Guerra et al. Journal Physics, 2016, 49(19)



$$\alpha = B \frac{(\hbar\omega - E_g)^2}{\hbar\omega}$$

$$\alpha = \frac{-\pi}{4} \frac{\alpha_0}{\beta \hbar\omega} Li_2[-e^{\beta(E-E_g)}]$$

Photoelectrochemical characterization



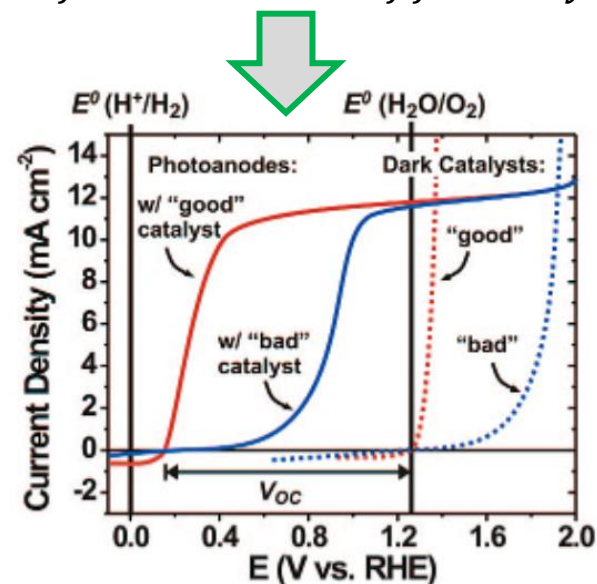
$$\eta_{PEC} = \eta_1 \cdot \eta_2 \cdot \eta_3 \cdot \eta_4$$

η_1 : Light harvesting efficiency

η_2 : Charge separation efficiency

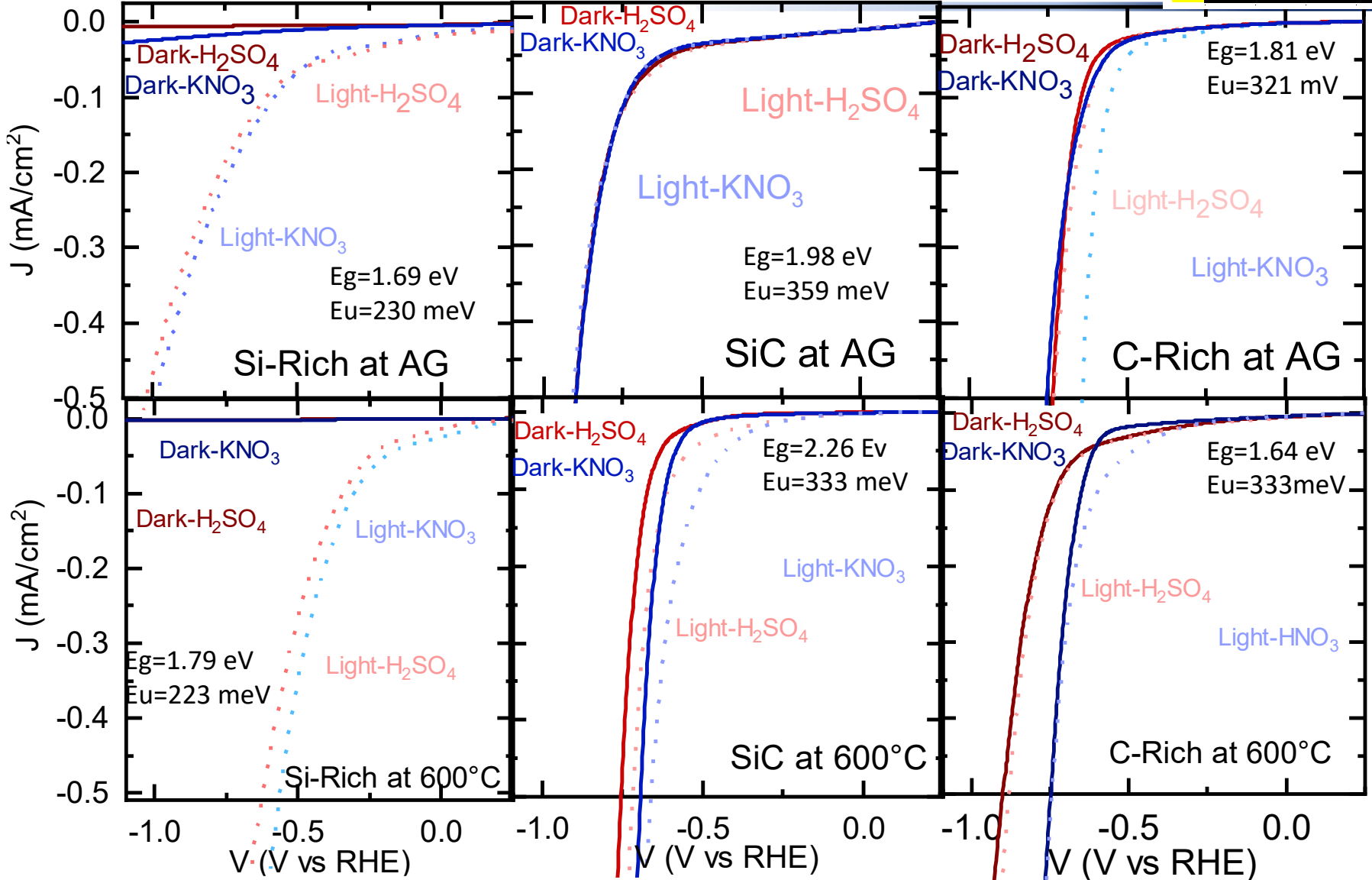
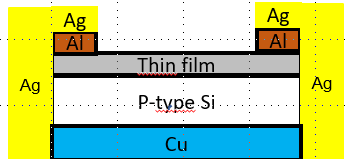
η_3 : Charge transport efficiency

η_4 : Surface reaction efficiency

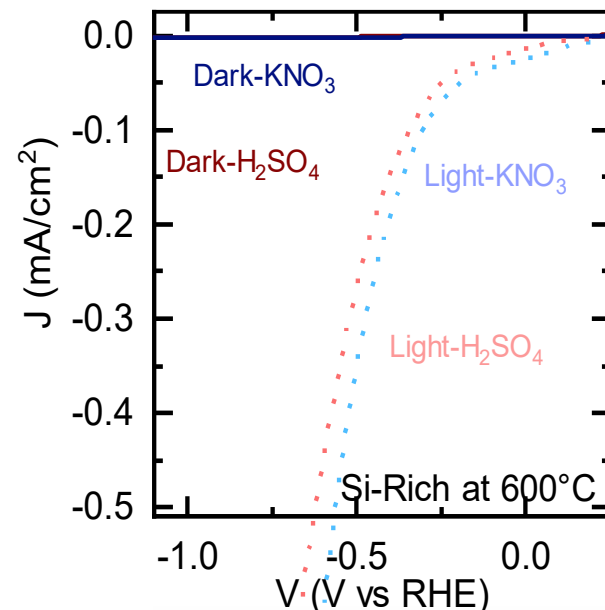
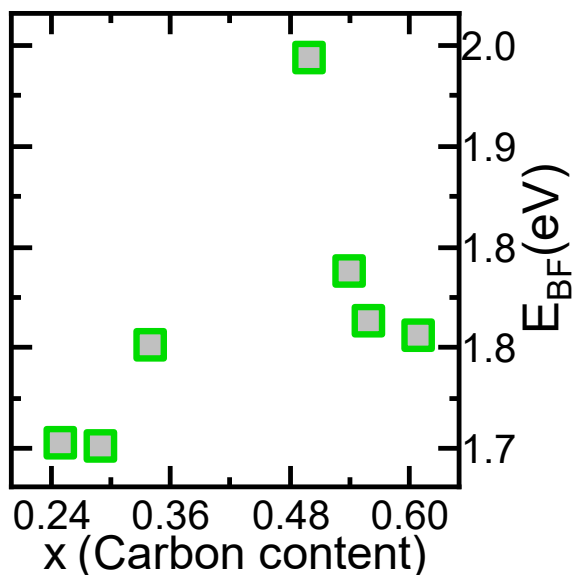
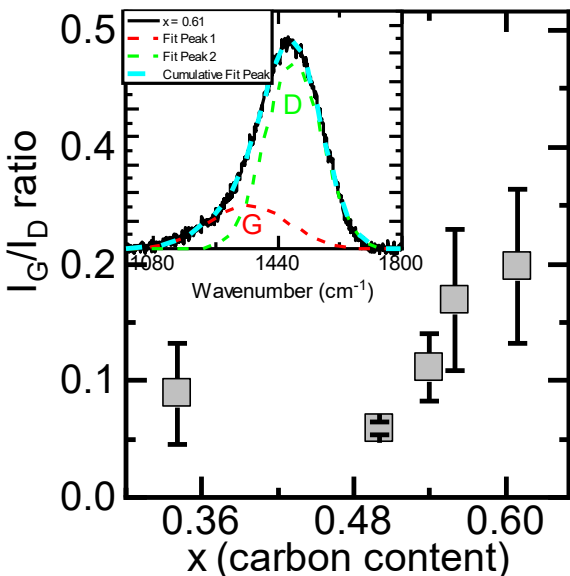


Michael G. Chem.Rev.2010,110,6446-6473

Photoelectrochemical characterization



Summary and future work



- ❑ Do electrolytes of SiC substoichiometric at $600^\circ C$ and quantify the ammonia production.
- ❑ Determine flat band potential and dopants through Mott-Schottky plots of SiC substoichiometric samples
- ❑ Do electrolytes of cocatalysis loading of silicon rich sample at AG and quantify the ammonia production.



Acknowledgements



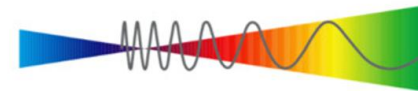
Prof. Dr. Andrés Guerra
guerra.jorgea@pucp.edu.pe



Prof. Dr. Kamala Nanda
@pucp.edu.pe



MatER
Materials Science and
Renewable Energies Group



CAMPUCP
CENTRO DE CARACTERIZACIÓN DE MATERIALES



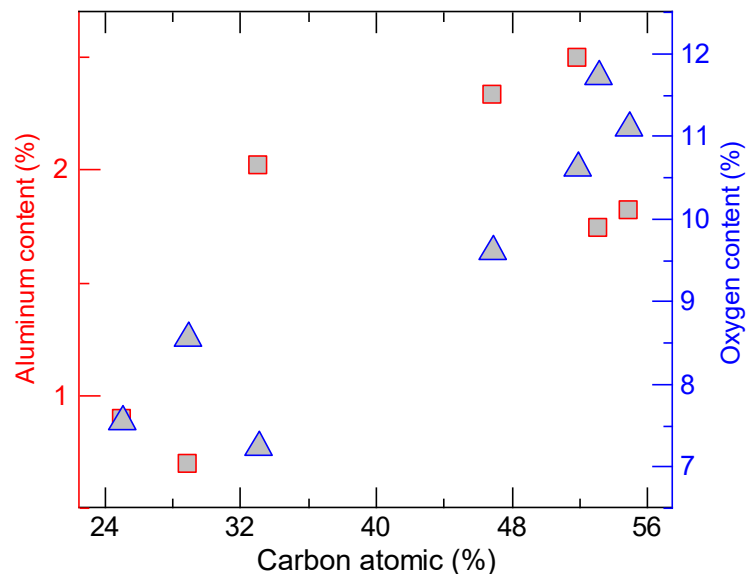
CONCYTEC
CONSEJO NACIONAL DE CIENCIA,
TECNOLOGÍA E INNOVACIÓN

**Pro
CIENCIA**

THANKS

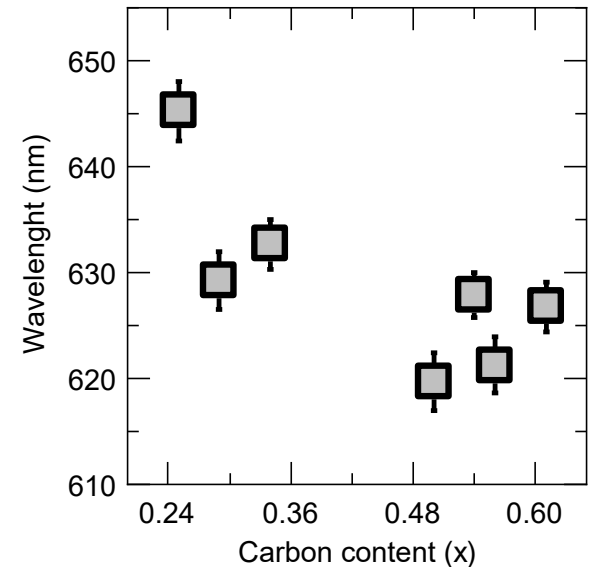
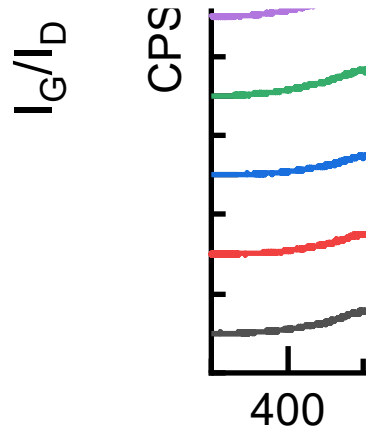
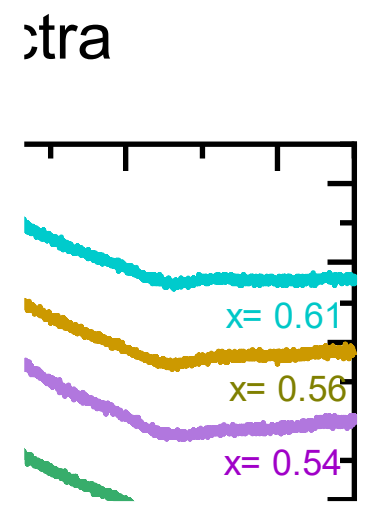
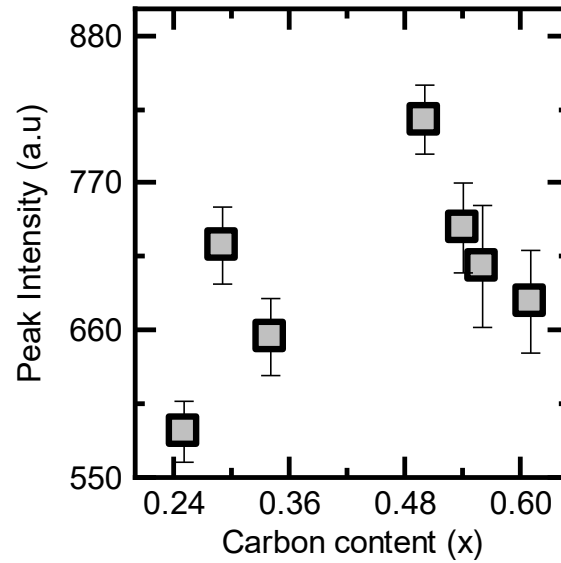
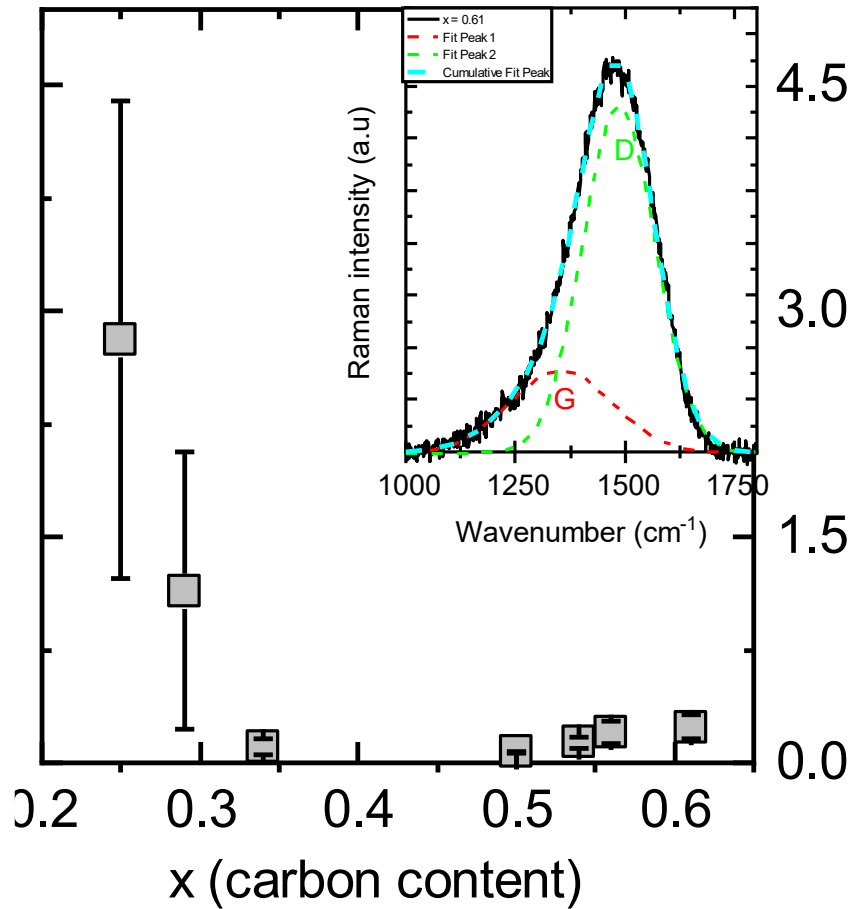


EDS measurement

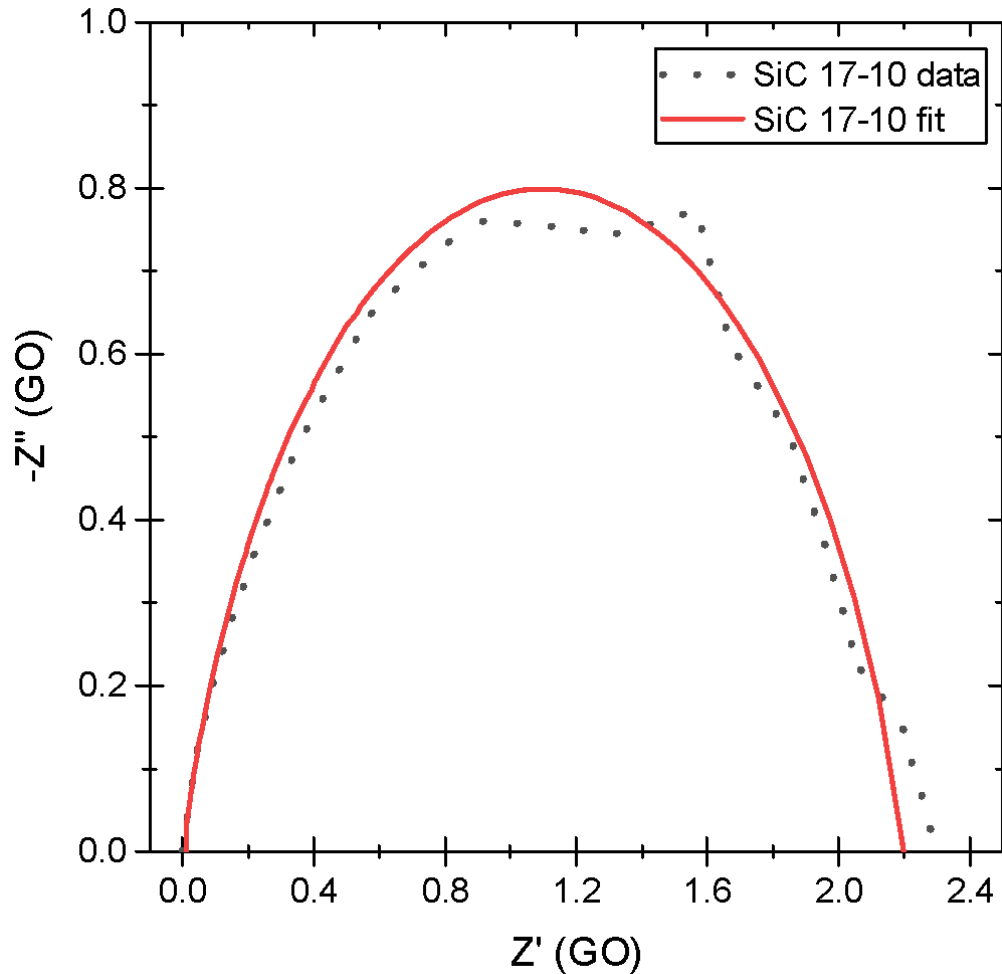


	Measurements	Chemical composition (Atomic %)			
		Si	C	O	Al
	SEM-EDS (CaF2 - 5 KeV)	66.51	25.06	7.54	0.89
	SEM-EDS (CaF2-4.5 KeV)	61.85	28.91	8.55	0.69
	SEM-EDS (CaF2- 4KeV)	57.16	33.07	7.24	2.02
	SEM-EDS (CaF2 – 4KeV)	41.11	46.95	9.60	2.33
	SEM-EDS (CaF2 – 4KeV)	34.99	51.90	10.62	2.49
	SEM-EDS(CaF2-3.5KeV)	33.35	53.15	11.73	1.74
	SEM-EDS(CaF2-4KeV)	30.38	54.91	11.10	1.82

Index Graphitization

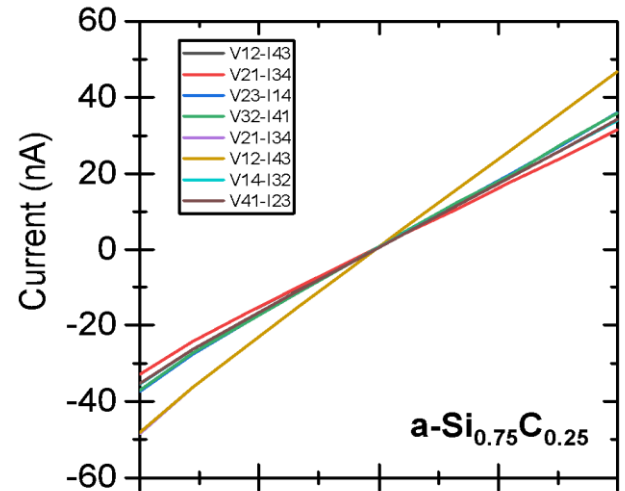
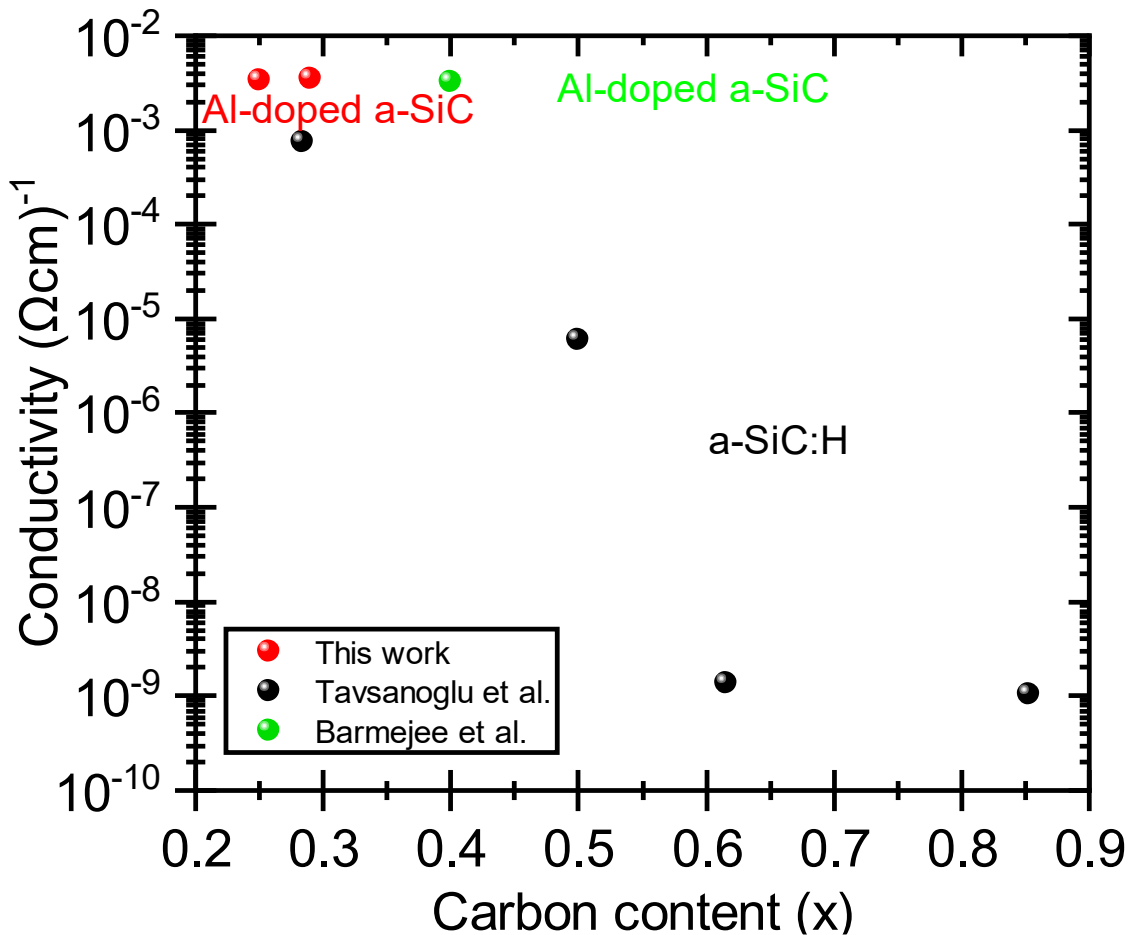


EIS semiconductor



Parameters (Unit)	Value
Bulk resistance ($G\Omega$)	2.2
CPE (pF)	0.54
Equivalent Capacitance (pF)	0.10
index	0.80
Maximum frequency (Hz)	713
Conductivity (S/m)	0.455×10^{-9}
Relative permittivity	14

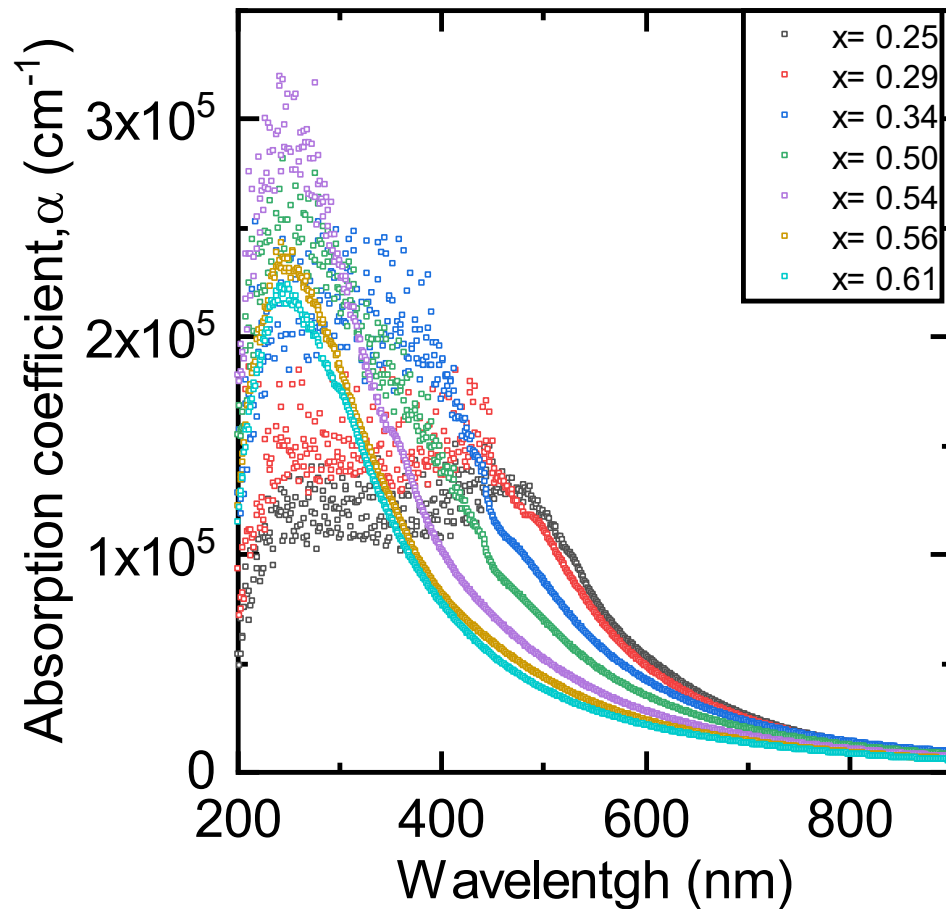
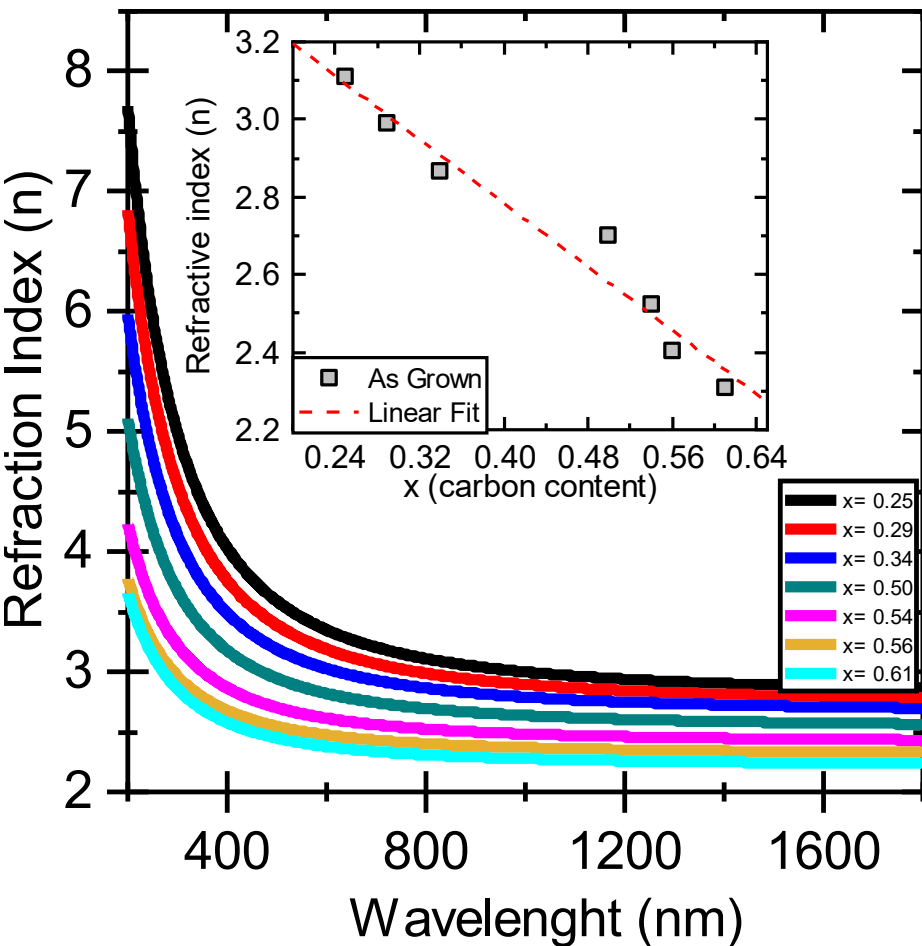
Electrical measurement



Samples	Conductivity ($\Omega^{-1} \text{ cm}^{-1}$)
σ (x=0.25)	3.53×10^{-3}
σ (x=0.29)	3.45×10^{-3}
σ (x=0.34)	-----
σ (x=0.50)	-----
σ (x=0.56)	-----
σ (x=0.58)	-----
σ (x=0.61)	-----

Conductivity values of SiC films [8][9]

Optical measurement



EIS measurement

